Ref #	Hits	Search Query	DBs	Default Operato r	Plural s	Time Stamp
S1	115841	(SOI (silicon near5 insulat\$3))	US-PGPU B; USPAT; USOCR	OR	ON	2005/06/21 19:27
S2	72073	S1 and (source drain)	US-PGPU B; USPAT; USOCR	OR	ON	2005/06/21 19:27
S3	45960	S2 and gate	US-PGPU B; USPAT; USOCR	OR	ON	2005/06/21 19:28
<b>S4</b>	217188	(STI (shallow near5 trench near5 isolat\$3))	US-PGPU B; USPAT; USOCR	OR	ON	2005/06/21 19:28
S5	5690	S3 and S4	US-PGPU B; USPAT; USOCR	OR	ON	2005/06/21 16:33
S6	1706	S5 and epitaxial\$3	US-PGPU B; USPAT; USOCR	OR	ON	2005/06/21 16:33
<b>S7</b>	1661	S6 and trench	US-PGPU B; USPAT; USOCR	OR	ON	2005/06/21 16:33
S8	1669	S6 and (trench recess groove)	US-PGPU B; USPAT; USOCR	OR	ON	2005/06/21 16:34
S9	684	S8 and (thermal near8 oxid\$3)	US-PGPU B; USPAT; USOCR	OR	ON	2005/06/21 16:34
S10	797	S8 and (thermal\$3 near8 oxid\$3)	US-PGPU B; USPAT; USOCR	OR	ON	2005/06/21 16:34
S11	684	S9 and S10	US-PGPU B; USPAT; USOCR	OR	ON	2005/06/21 16:35
S12	36576	(SOI (silicon near5 insulat\$3))	EPO; JPO; DERWENT ;	OR	ON	2005/06/21 19:27
S13	7656	S12 and (source drain)	IBM_TDB EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/06/21 19:28
S14	5837	S13 and gate	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/06/21 19:28

S15	61	S14 and (STI (shallow near5 trench near5 isolat\$3))	EPO; JPO; DERWENT	OR	ON	2005/06/21 19:29
			; IBM_TDB			